



ITW
PATENT
8007-1118

IN THE U.S. PATENT AND TRADEMARK OFFICE

In re application of

Masaru HOSOKAWA et al.

Conf. 4713

Application No. 10/594,567

Group 1793

Filed September 27, 2006

Examiner S. Abu Ali

MATERIAL FOR CHEMICAL VAPOR DEPOSITION AND THIN FILM FORMING
METHOD

AMENDMENT

Assistant Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

May 23, 2008

Sir:

In response to the Official Action mailed May 7, 2008,
please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing
of claims which begins on page 2 of this paper.

Remarks begin on page 6 of this paper.